Courses are subject to revision and final approval.

Electrical Engineering

963B*. Advanced Topics in Analog Circuits (MTC)
Spring of odd-numbered years. 3(3-0)
F: EE 827: R: NONE
Subtitle: Advanced Circuit Analysis.

963A*. Advanced Circuit Analysis
Spring of odd-numbered years. 3(3-0)
F: EE 831: R: NONE

960*. Advanced Topics in Control (MTC)
Fall. 3(3-0) May re enroll for a maximum of 6 credits.
F: EE 827: R: NONE
Subtitle: Adaptive Control, Nonlinear Control
QP: EE 826

960B*. Nonlinear Control
Fall. 3(3-0)
F: EE 827: R: NONE
Model reference adaptive control in continuous time and discrete time. Lyapunov and hyperstability approaches, adaptive observers, self-tuning regulators, design using pole-zero assignments. Minimum variance control and LQG control.
QP: EE 827 QA: EE 965

966B*. Multidimensional Signal Processing
Spring. 3(3-0)
F: EE 866: R: NONE
QP: EE 880 QA: NONE

966A*. Discrete Time Processing of Speech Signals
Fall. 3(3-0)
F: EE 866, EE 466R or EE 863: R: NONE
QP: EE 880 QA: EE 901

966C*. Detection and Estimation Theory
Spring. 3(3-0)
F: EE 847, EE 863: R: NONE
Communication channels, noise models, hypothesis testing problems, signal detection by Bayesian minimax, and Neyman-Pearson criteria. Performance evaluation using ROC. Bayesian and maximum likelihood parameter estimation. Kalman-Bucy filtering.
QP: EE 847 EE 863 QA: EE 845

989*. Advanced Topics in Plasma (MTC)
Fall of odd-numbered years. 3(3-0)
F: EE 855, EE 850: R: NONE
QP: EE 850 QA: EE 899

989A*. Plasma Processing for IC Fabrication
Fall of odd-numbered years. 3(3-0)
F: EE 855, EE 850: R: NONE
Process requirements. Plasma reactors. Etching and deposition applications. Beam ion beam processing.
QP: EE 850 EE 850 QA: EE 989

999*. Doctoral Dissertation Research
Fall, Spring, Summer. 1 to 12 credits.
May re enroll for a maximum of 9 credits.
Process requirements. Plasma reactors. Etching and deposition applications. Beam ion beam processing.
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English

090*. Intensive English for International Students
May re enroll for a maximum of 45 credits.
R: Permission of English Language Center
Explanation and intensive practice of basic English skills. Students are tested and placed in groups, from beginning to advanced, depending on their need.
QA: ENG 091 ENG 092 ENG 093 ENG 094 ENG 095

091*. English Structure for International Students
Fall, Spring. 3(3-0)
R: Permission of English Language Center
Explanation and practice of advanced grammatical structures of English in relation to written communication. Heavy emphasis on editing skills.
QA: ENG 091

092*. Academic Communication Skills for International Students
Fall, Spring. 3(3-0)
R: Permission of English Language Center
Intensive speaking and listening practice of spoken academic English, lecture-listening and note-taking strategies developed. Oral communication skills improved through discussion, reading and classroom presentations.
QA: ENG 092

093*. Academic English for International Students
Fall, Spring. 8(10-0) May re enroll for a maximum of 12 credits.
R: Permission of English Language Center
Integrative reading and writing strategies for academic purposes. Includes vocabulary development, intensive and extensive reading and critical reading skills. Develops academic writing style and editing strategies.
QA: ENG 094 ENG 095